L Number	Hits	Search Text	DB	Time stamp
1	213	(((((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or	USPAT; US-PGPUB;	2004/05/06 16:20
		tantalum)) and ((Cr\$O\$N or (chrom\$4 with	EPO; JPO;	
		(oxide or oxy\$4) with nitr\$4)))) and (mask or photomask or reticle) and (resist or	DERWENT	
		photoriesist)) and ((430/5).CCLS.)		
2	182	(430/296.ccls. and ((Resist or photoresist)	USPAT;	2004/05/06
		with ((hard or metal or etch\$3) adj (layer or film or mask)))) and (Cr or chrom\$4 or W or	US-PGPUB; EPO; JPO;	16:25
		tungsten or Ta or tantalum)	DERWENT	
3	122	(((430/311).CCLS.) and ((hard or metal or	USPAT;	2004/05/06
		etch\$3) adj (layer or film or mask)) and (W or	US-PGPUB;	16:26
		tungsten or Ta or tantalum)) and (Cr\$O\$N or (chrom\$4 with (oxide or oxy\$4) with nitr\$4))	EPO; JPO; DERWENT	
4	86	(((430/322).CCLS.) and ((hard or metal or	USPAT;	2004/05/06
		etch\$3) adj (layer or film or mask)) and (W or	US-PGPUB;	16:28
		tungsten or Ta or tantalum)) and (Cr\$O\$N or	EPO; JPO;	
5	122	(chrom\$4 with (oxide or oxy\$4) with nitr\$4)) (216/53).CCLS.	DERWENT USPAT:	2004/05/06
	122	(210/33).0023.	US-PGPUB;	16:28
			EPO; JPO;	
			DERWENT;	
	33	((216/53).CCLS.) and (mask or photmask or	IBM_TDB USPAT;	2004/05/06
6	33	reticle)	US-PGPUB;	16:29
			EPO; JPO;	
			DERWENT;	
-	4	09/683929	IBM_TDB USPAT;	2003/11/22
-	1	09/003929	US-PGPUB;	16:52
			EPO; JPO;	
			DERWENT	
-	204	(UTR or (thin near (resist or photoresist))) and	USPAT; US-PGPUB;	2004/04/28 14:27
		((((hard or metal or etch\$3) adj (layer or film or mask)) and (W or tungsten or Ta or	EPO; JPO;	17.27
		tantalum)) and ((Cr\$0\$N or (chrom\$4 with	DERWENT	
		(oxide or oxy\$4) with nitr\$4))))		
-	1746	((((hard or metal or etch\$3) adj (layer or film	USPAT;	2004/04/28 14:27
		or mask)) and (W or tungsten or Ta or tantalum)) and ((Cr\$O\$N or (chrom\$4 with	US-PGPUB; EPO; JPO;	14:2/
		(oxide or oxy\$4) with nitr\$4)))) and (mask or	DERWENT	
		photomask or reticle).ti,ab.		
-	75	(UTR or (thin near (resist or photoresist))) and	USPAT;	2004/04/28
		(((((hard or metal or etch\$3) adj (layer or film	US-PGPUB; EPO; JPO;	14:28
		or mask)) and (W or tungsten or Ta or tantalum)) and ((Cr\$O\$N or (chrom\$4 with	DERWENT	
		(oxide or oxy\$4) with nitr\$4)))) and (mask or		
		photomask or reticle).ti,ab.)		